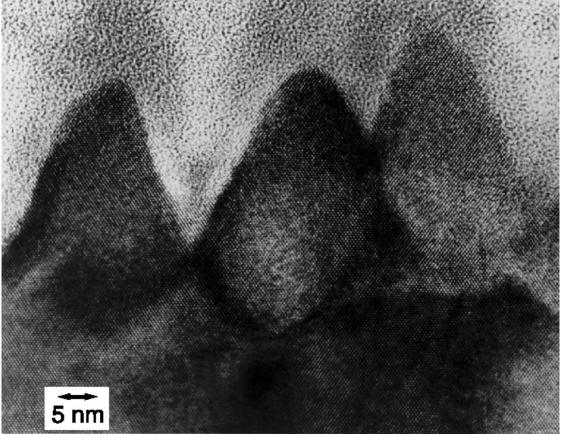


Ion Irradiation Simulations to Study Quantum Dot Formation in III-V Semiconductors Michael Y. Toriyama¹, Michael A. Lively^{2,3}, Brandon J. Holybee^{2,3}, and Jean-Paul Allain^{2,3,4}

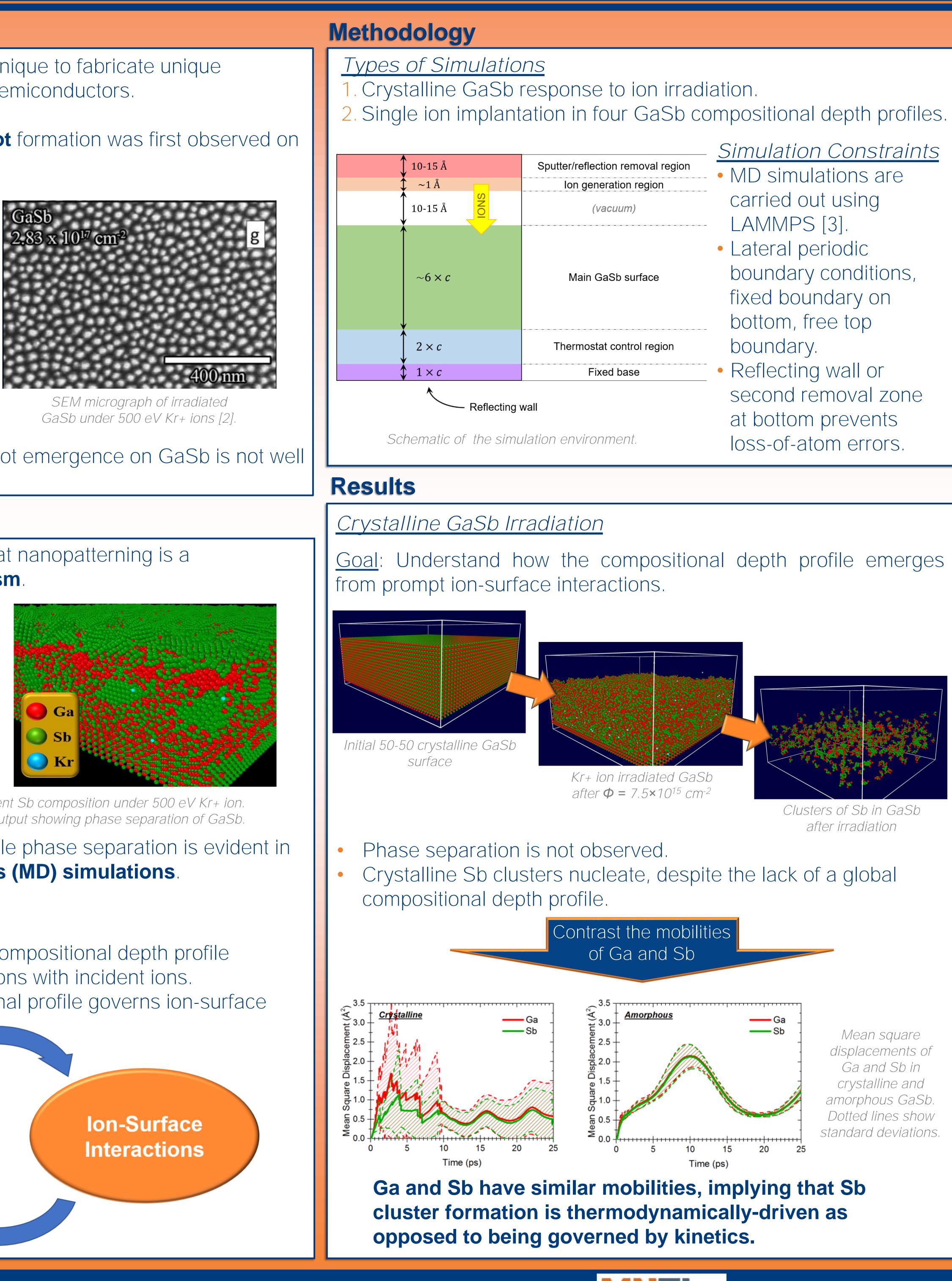
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Background

- Ion irradiation is a scalable technique to fabricate unique nanostructures on surfaces of semiconductors.
- Irradiation-induced quantum dot formation was first observed on gallium antimonide (GaSb) [1].



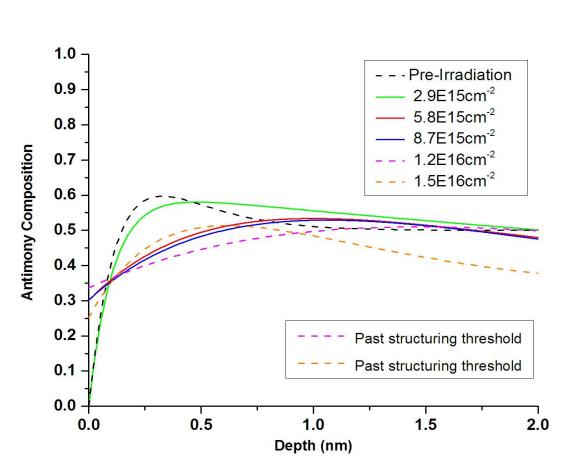
Cross-sectional TEM image of nanostructures on a GaSb surface [1].

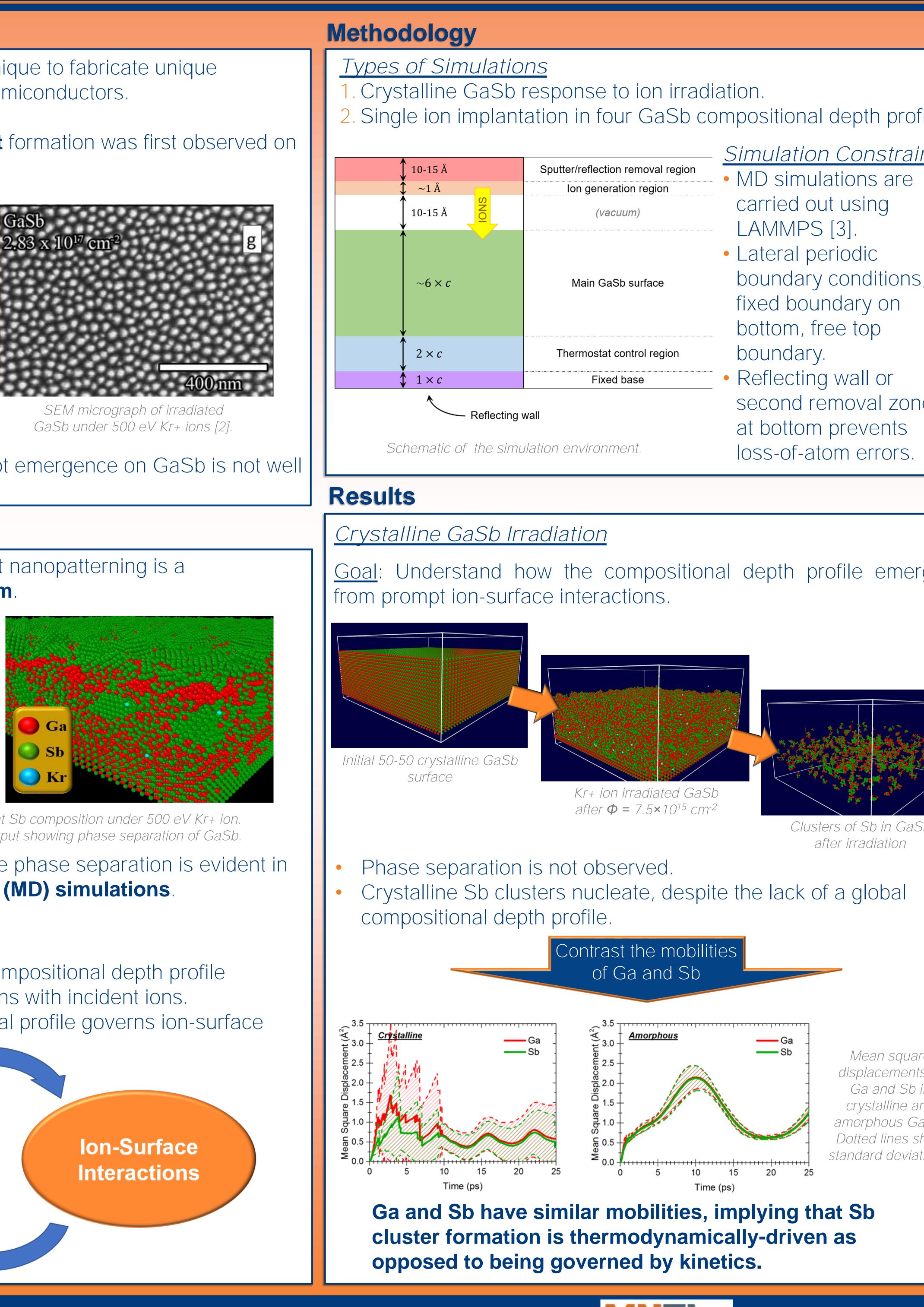


Theoretical model of quantum dot emergence on GaSb is not well developed.

Motivation

Recent experiments suggest that nanopatterning is a composition-driven mechanism.





(Left) ARAES data on the depth-dependent Sb composition under 500 eV Kr+ ion. (Right) Molecular Dynamics simulation output showing phase separation of GaSb.

The formation of such metastable phase separation is evident in atomistic Molecular Dynamics (MD) simulations.

Key Focuses:

- Understand how the GaSb compositional depth profile responds to prompt interactions with incident ions.
- Analyze how the compositional profile governs ion-surface interactions.

GaSb Compositional **Depth Profile**

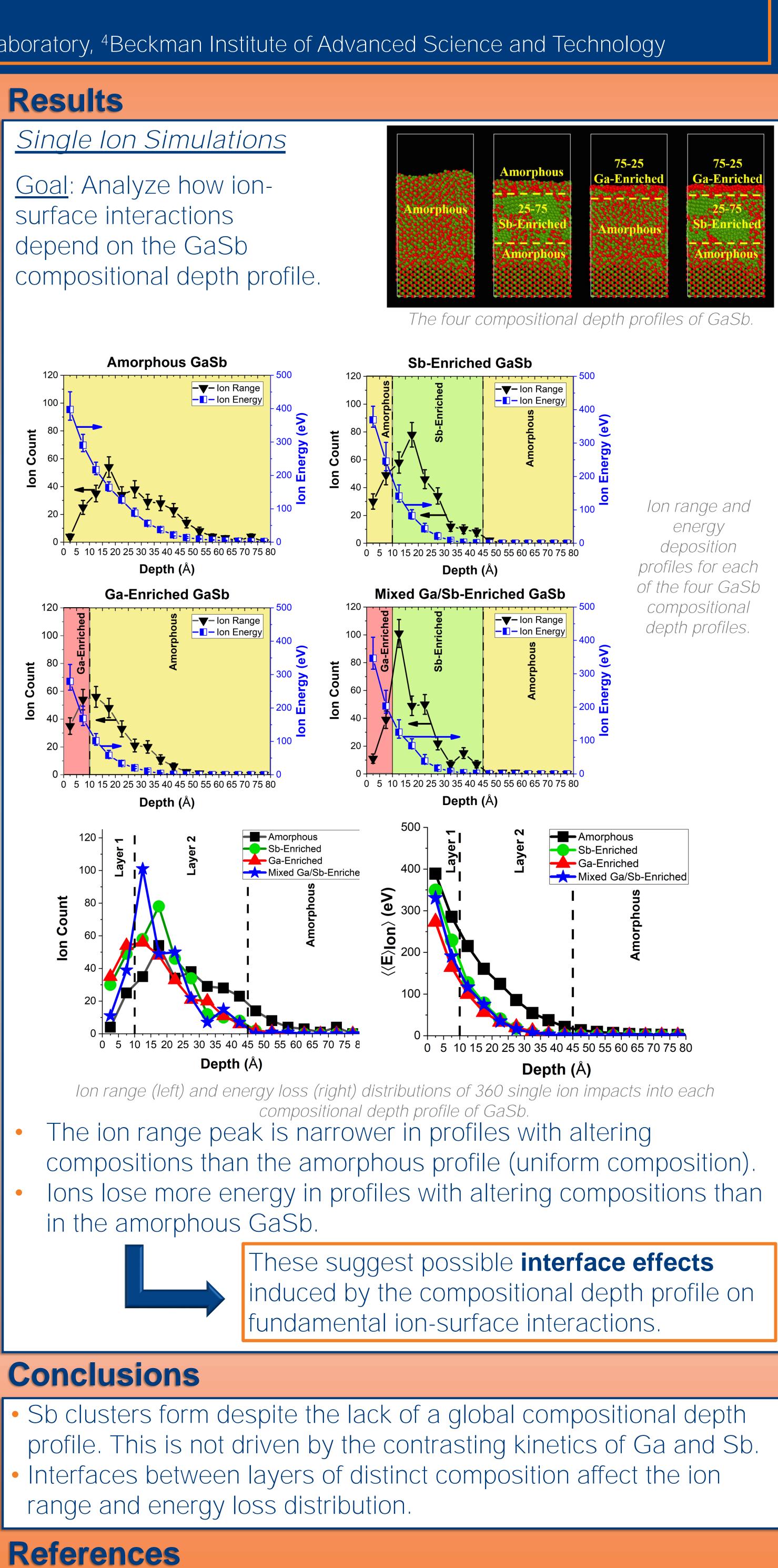
http://cpmi.uiuc.edu Center for Plasma-Material Interactions

Simulation Constraints

- boundary conditions,
- second removal zone

Mean square displacements of Ga and Sb in crystalline and amorphous GaSb. Dotted lines show standard deviations.

Results



[1] S. Facsko, T. Dekorsy, C. Koerdt, C. Trappe, H. Kurz, A. Vogt, and H. Hartnagel, Science 285, 1551-1553 (1999). [2] El-Atwani, O., Norris, S.A., Ludwig, K., Gonderman, S., and Allain, J.P., Sci. Rep. 5, 18207 (2015) [3] S. Plimpton, J. Comp. Phys. 117, 1-19 (1995)





